



Poster Sessions

313. PTB Seminar VUV and EUV Metrology



Poster List

Tuesday Oct 22 & Wednesday Oct 23

No.	Submitting author	Title	Institute/Company
1	H. Kirschner	How Metrology can improve Photoemission Tomography	PTB
2	A. Sokolov	Design, fabrication and characterization of highly efficient multilayer blazed gratings for the tender X-ray region	HZB
3	R. Geckeler	Advancing deflectometric form measurement of beamline optics: Current state and future strategies	PTB
4	N. Gutiérrez-Luna	High-reflectance Al mirrors protected with hot-deposited MgF ₂ or AlF ₃	GOLD-IO-CSIC
5	T. Siefke	Wire grid polarizer for VUV applications	FSU Jena
6	V. Zabrodskii	VUV Silicon Avalanche Detector	Ioffe RAS
7	J. Emmelkamp	Simulation model for the oxidation of Ru nanolayers under oxidizing/reducing plasma conditions	TNO
8	N.I. Chkalo	Cr/Sc/B ₄ C multilayer mirrors with enhanced reflectance in "water window"	IPM RAS
9	A. Yakshin	Structural analysis of ion polished W/Si soft X-ray multilayer reflectors	U Twente
10	F. Melsheimer	Laser heating of pinch plasma for EUV emission: Determination of plasma parameters and spectrally resolved tomography	FZ Jülich
11	L. Bahrenberg	In-lab EUV spectroscopy for the characterization of optical properties and nanoscale geometries	RWTH
12	B. Lüttgenau	Modelling and experimental evaluation of near-field intensity distributions for high-resolution EUV transmission masks	RWTH
13	M. Ghafoori	Development of a multiangular broadband scatterometer for critical dimension metrology at EUV wavelength	RWTH EUV
14	S. Glabisch	Reconstruction of nanoscale gratings based on EUV reflectometry data and machine learning techniques	RWTH TOS
15	O. Maryasov	Diffraction grating characterization with grazing incidence EUV scattering	RWTH
16	J. Feikes	First experiment towards „Steady State Micro Bunching“ successfully performed at the Metrology Light Source	HZB
17	A. Fernández Herrero	Limits on the application of the Debye-Waller Factor in GISAXS	PTB
18	M. Ruiz-Lopez	Analysis of FLASH beamlines caustic supported by wavefront simulations	DESY



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